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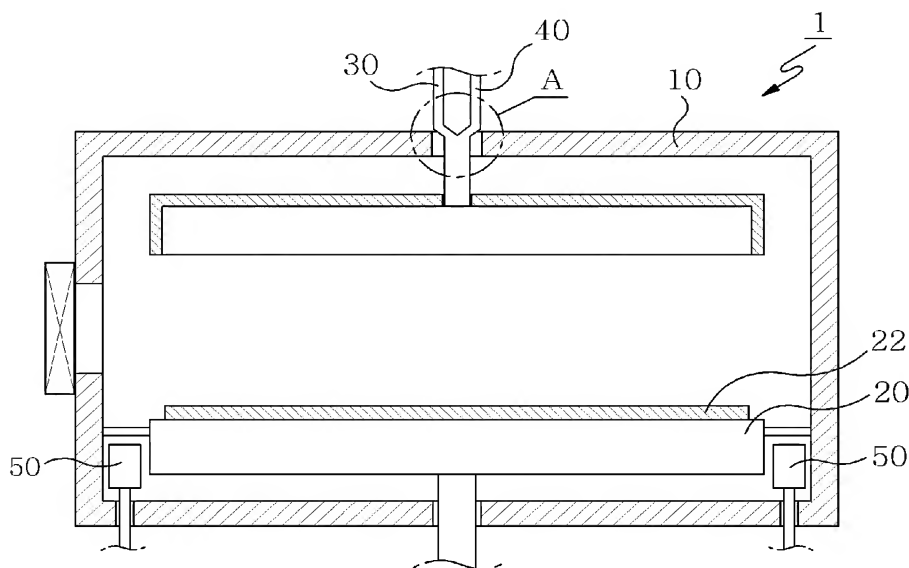
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[Continued on next page]

(54) Title: METHOD FOR FORMING ORGANIC LIGHT-EMITTING LAYER



(57) Abstract: Disclosed herein is a method for forming a light-emitting layer on an industrial scale via chemical vapor deposition or molecular layer deposition. According to the method, a metal-containing material and an 8-hydroxyquinoline derivative having stable vapor pressure characteristics are used as raw materials and are vaporized.



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